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INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Applicant: Shunpei YAMAZAKI

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U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
<i>RLG</i>	5,923,962	7/13/99	Ohtani et al.	_____	_____	
<i>RLG</i>	5,643,826	7/1/97	Ohtani et al.	_____	_____	

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation Yes No
<i>RLG</i>	7-130652	5/19/95	Japan	_____	_____	Abstract
<i>RLG</i>	9-312260	12/2/97	Japan	_____	_____	Abstract
<i>RLG</i>	64-31466	2/1/89	Japan	_____	_____	Abstract
<i>RLG</i>	1-270310	10/27/89	Japan	_____	_____	Abstract
<i>RLG</i>	7-263697	10/13/95	Japan	_____	_____	Abstract
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<i>RLG</i>	10-229201	8/25/98	Japan	_____	_____	Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	C.S. McCormick et al., "Low temperature fabrication of amorphous silicon thin film transistors by dc reactive magnetron sputtering", J. Vac. Sci. Technol. A 15(5), September/October 1997, pp. 2770-2776.

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